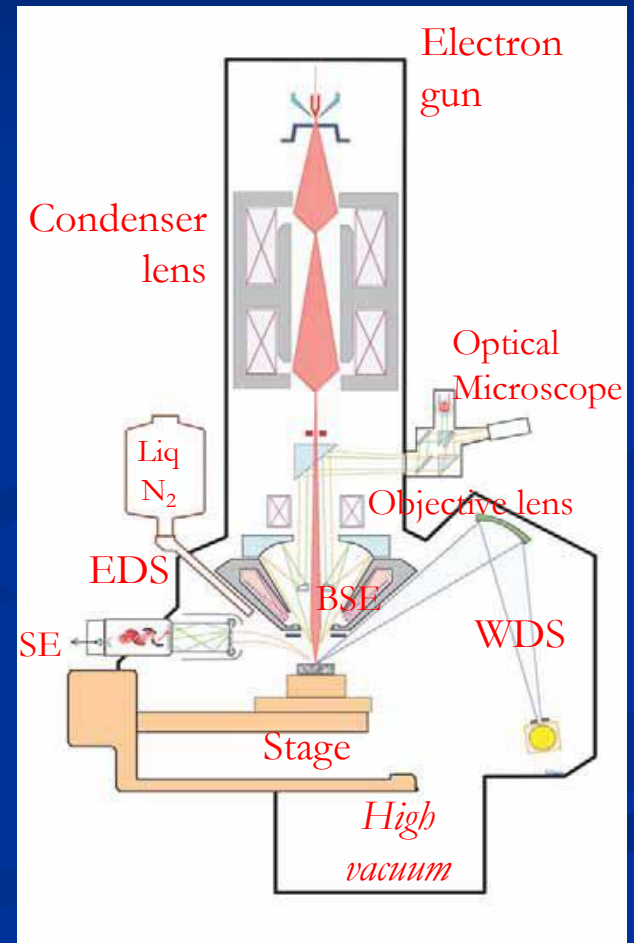
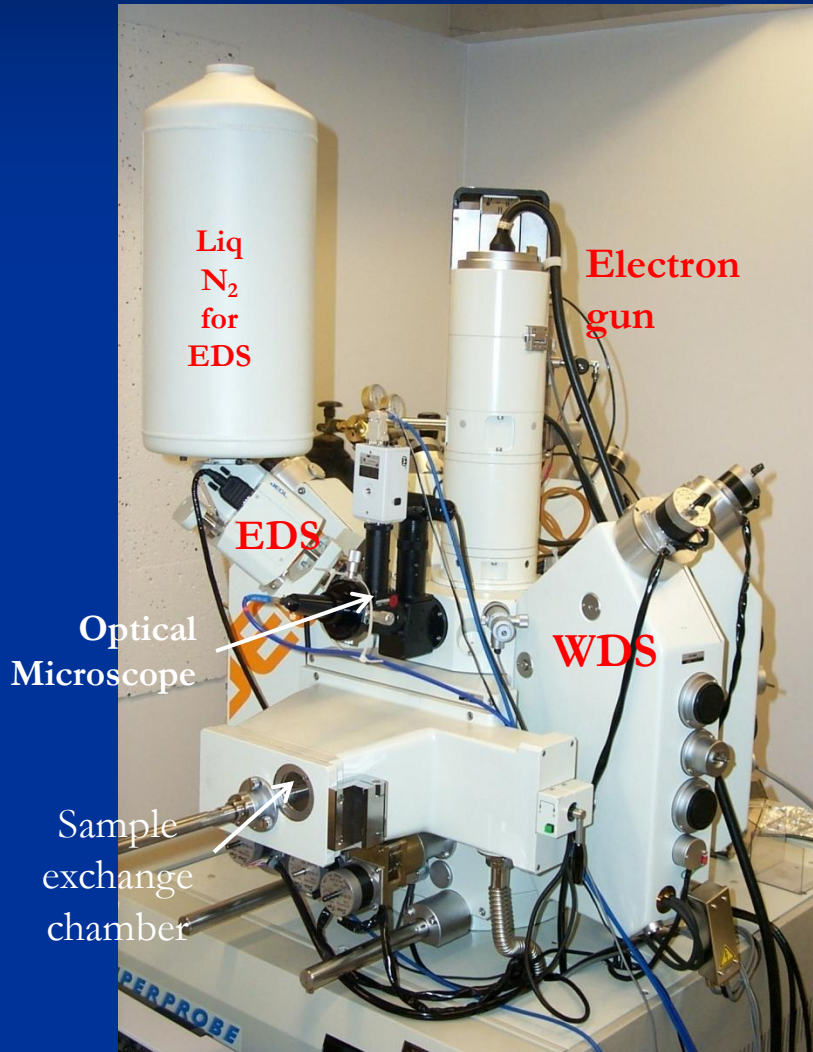


JEOL JXA-8200 Superprobe

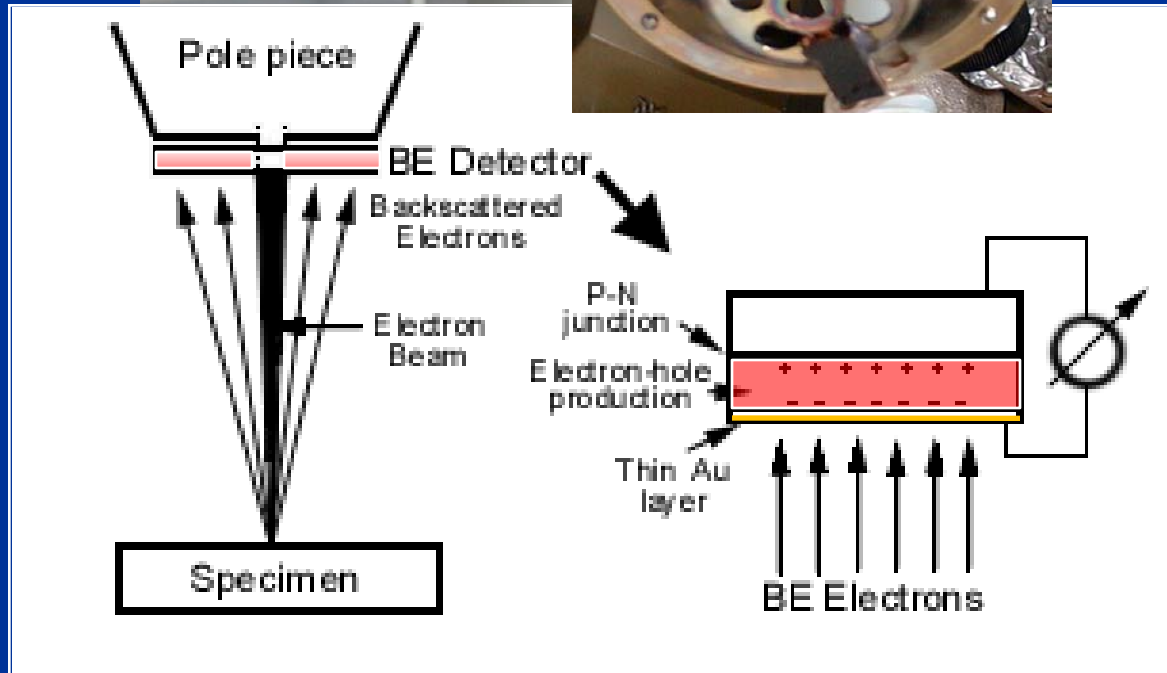
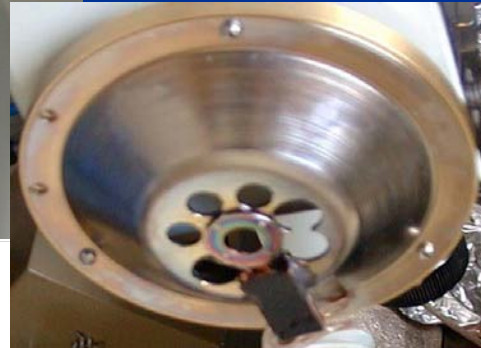


Perpendicular geometry

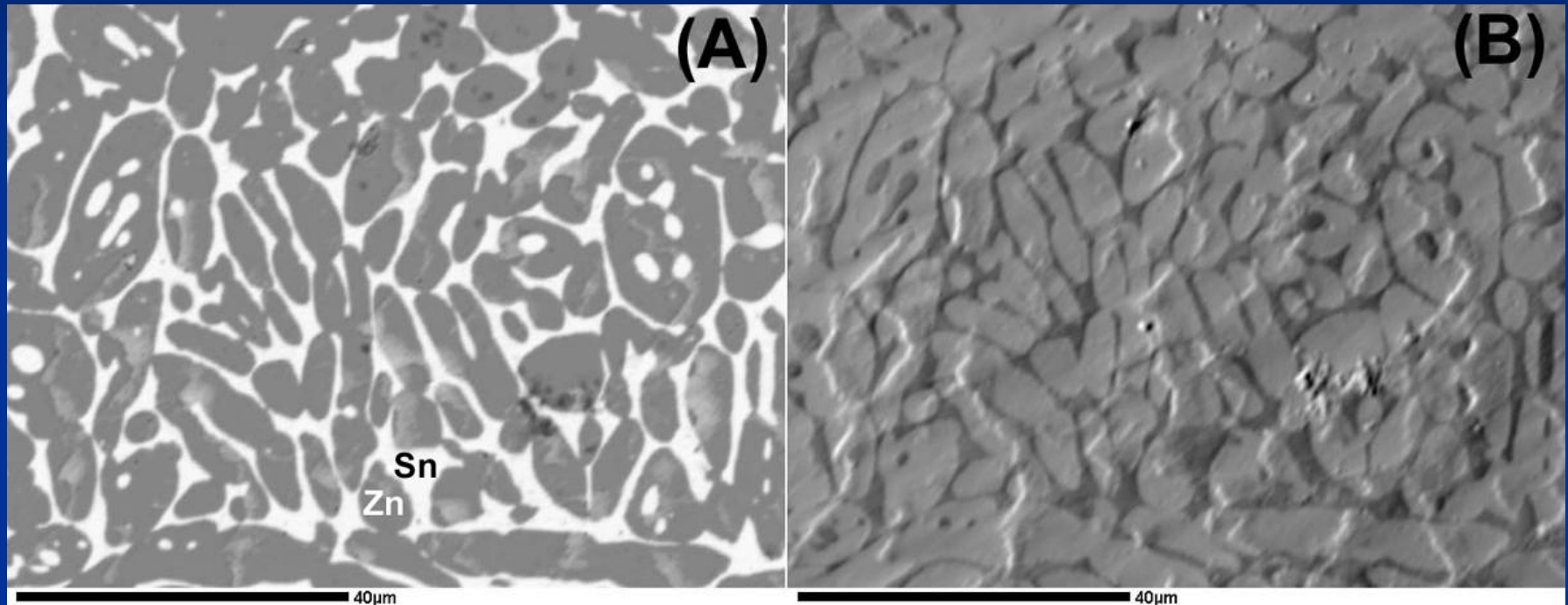
Back-scattered electron detector



Top view of specimen



Compositional and topographic imaging with BSE



Scanning backscattered electron images of a Zn-Sn composite collected through a solid-state diode detector in (A) A+B, or compositional mode; (B) A-B, or topographic mode

A+B
Compositional
mode

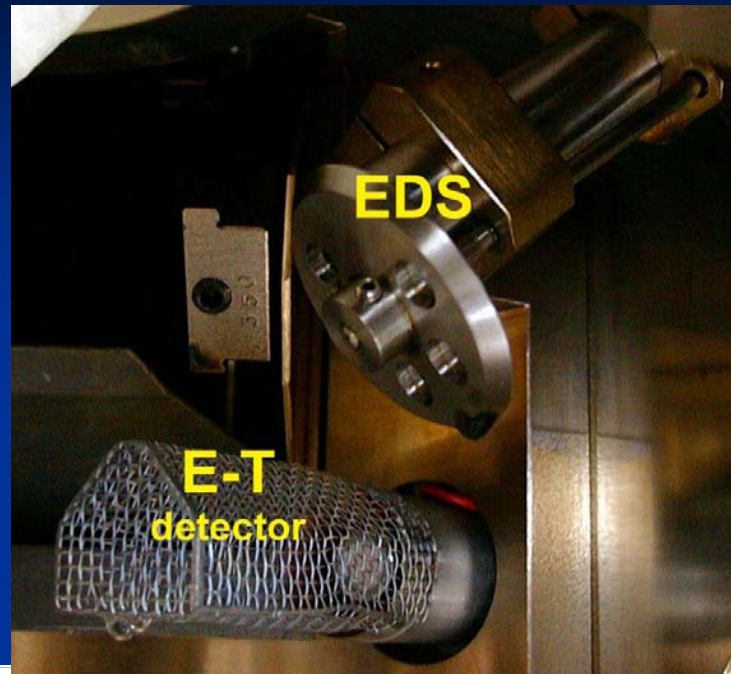
A-B
Topographic
mode

Secondary electrons

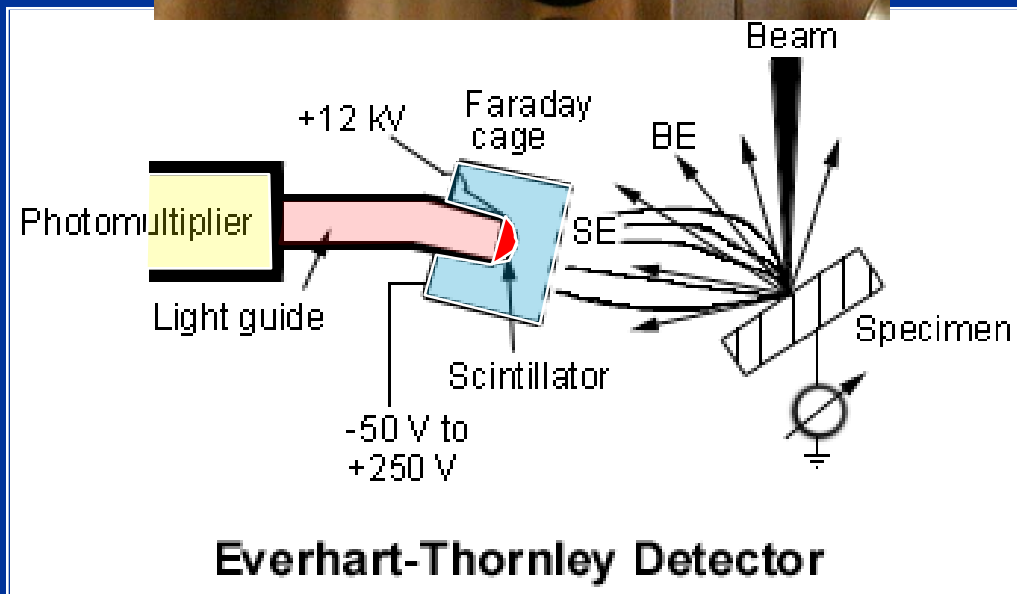
- Specimen electrons mobilized by electron beam through inelastic scattering
- Secondary electrons have lower energy compared to backscattered electrons

(useful in studying surface topography)

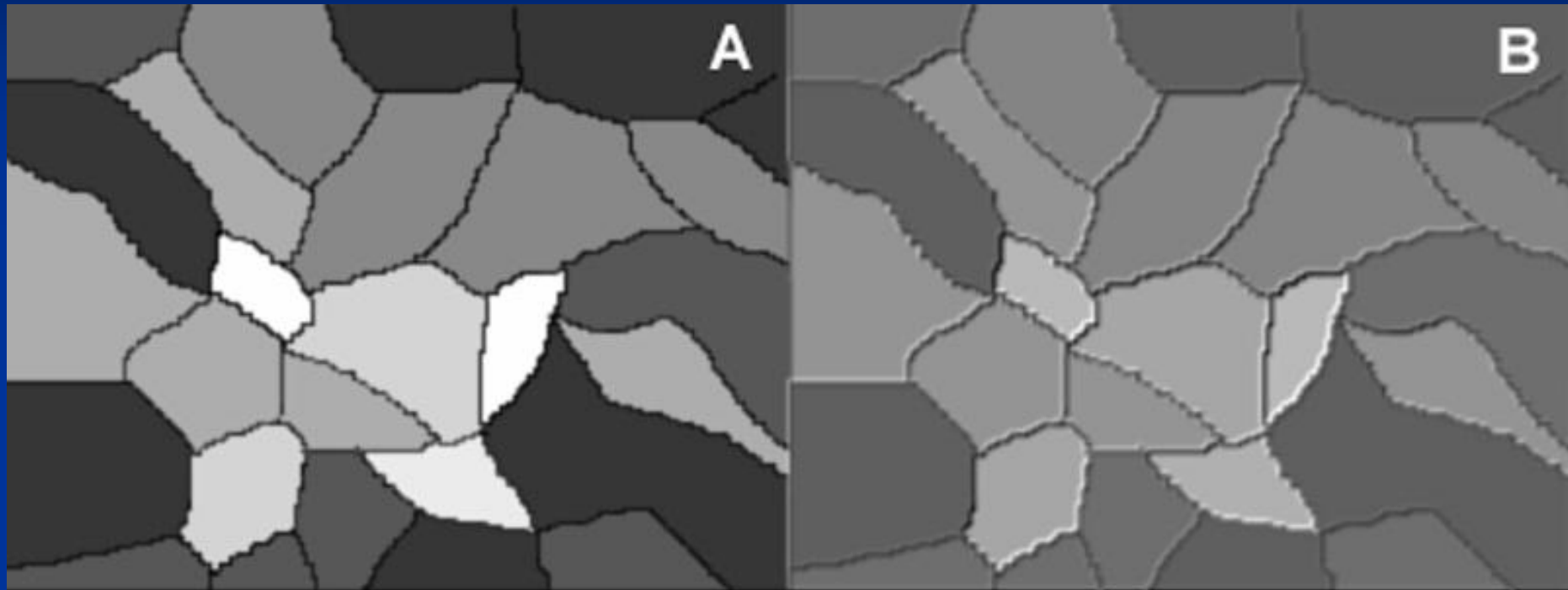
Secondary electron detector



Side view of specimen



Secondary electron imaging



(A) negatively biased, (B) positively biased E-T detector

-ve Faraday cage bias

less SE

less topographic contrast

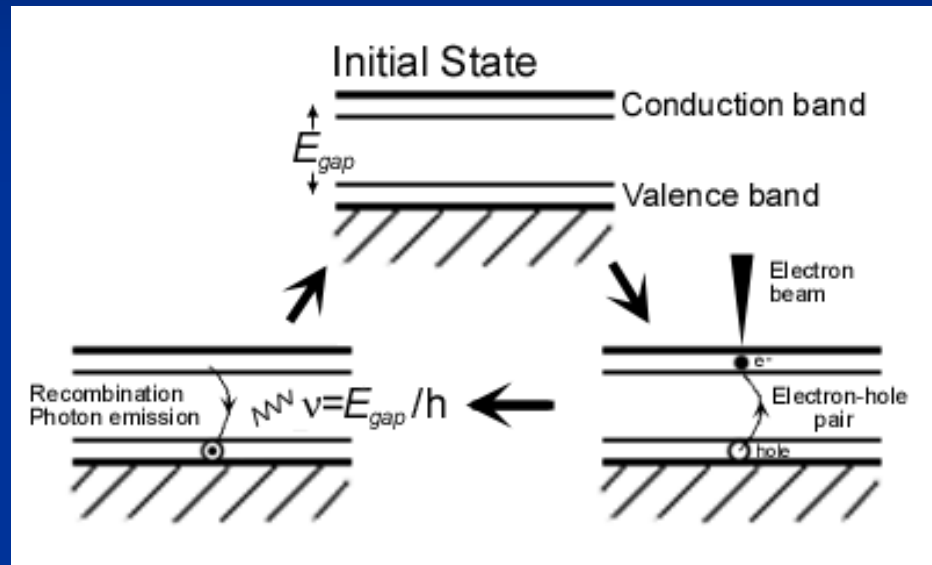
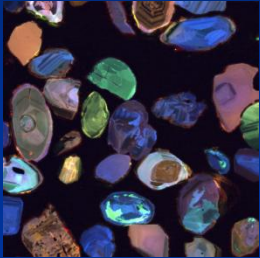
+ve Faraday cage bias

more SE

better topographic contrast

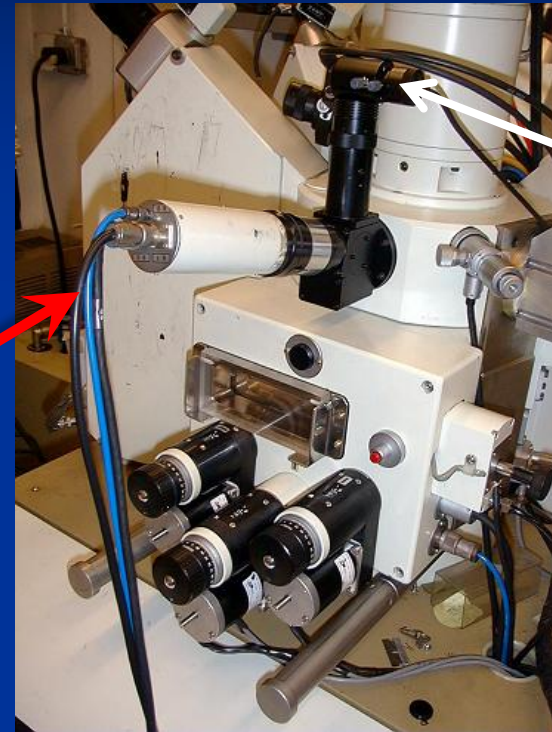
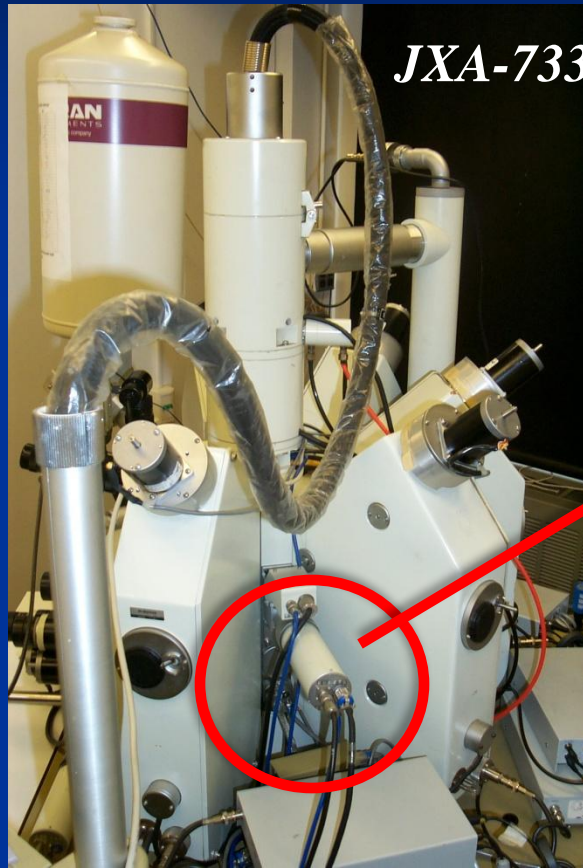
Cathodoluminescence

Light generated from sample through electron beam interaction



- *Band gap energy, E_{gap} , is a property of the semiconductor*
- *Trace impurities change E_{gap} by adding additional energy states in the band gap*

Cathodoluminescence detector



Photomultiplier for secondary electron imaging is used as CL detector
Optical arrangement is the same as for the optical microscope

Cathodoluminescence spectrometer

Optical microscope camera (not used)

Optical microscope light (turned off)

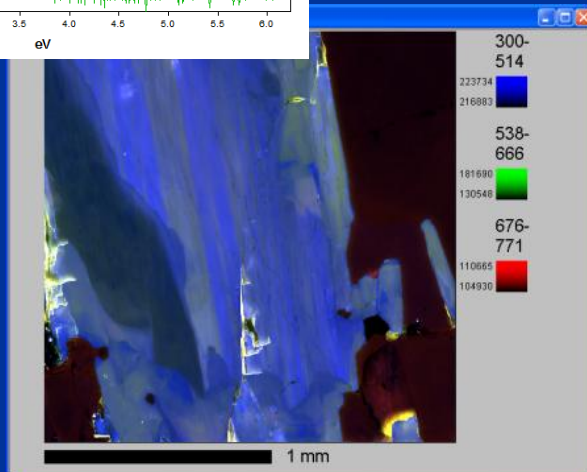
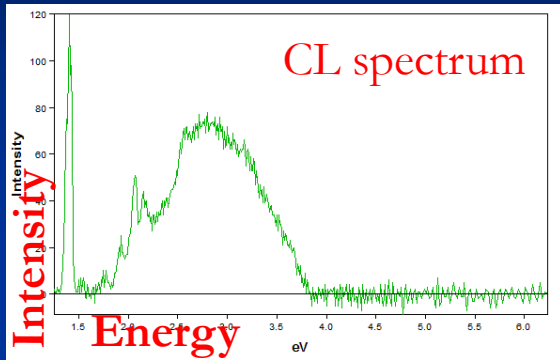


JXA-8200

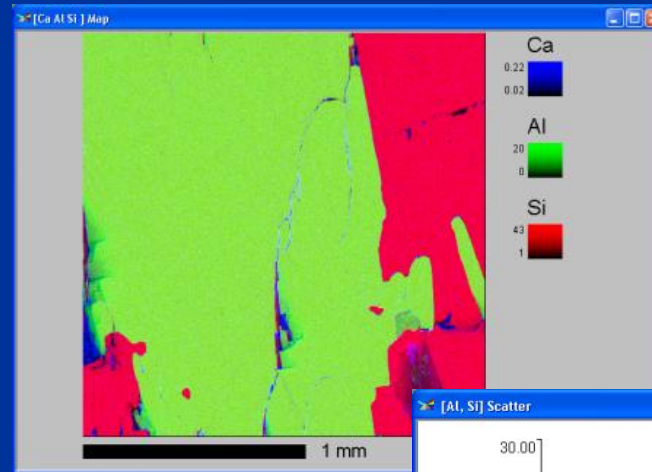


Optical spectrometer

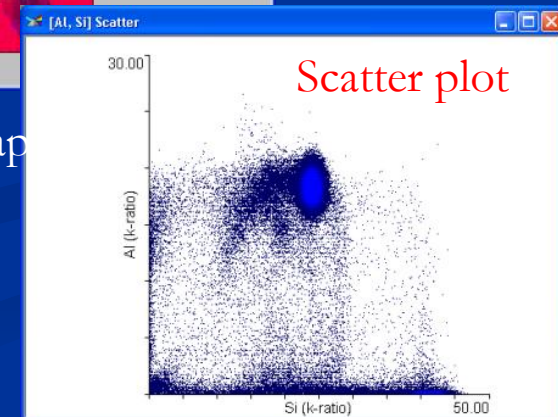
Integrated CL and X-ray spectrometry



3 band CL map

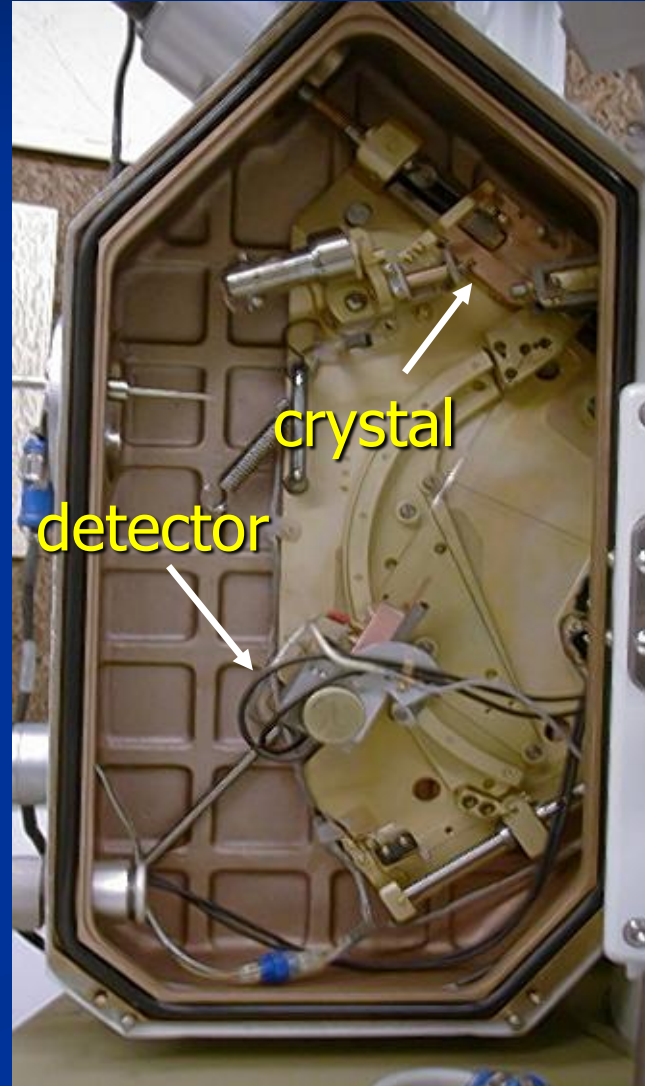


3 element X-ray map

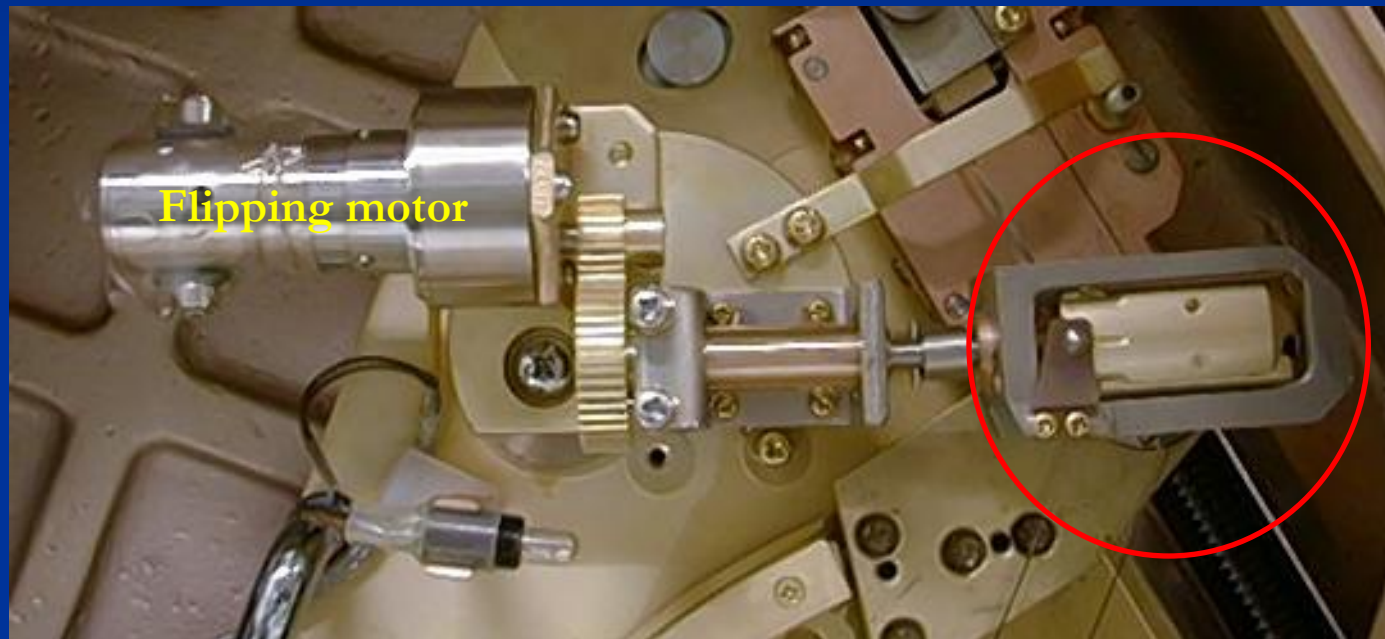


CL wavelength band may be correlated with an element

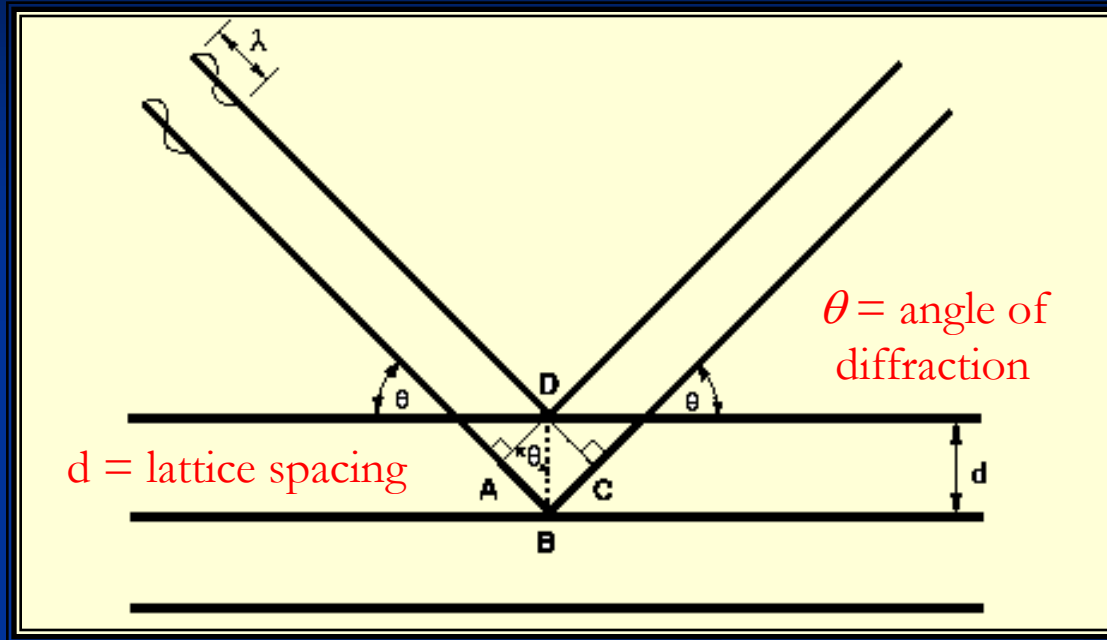
Wavelength Dispersive Spectrometer (WDS)



WDS Analyzing crystal



Bragg's Law

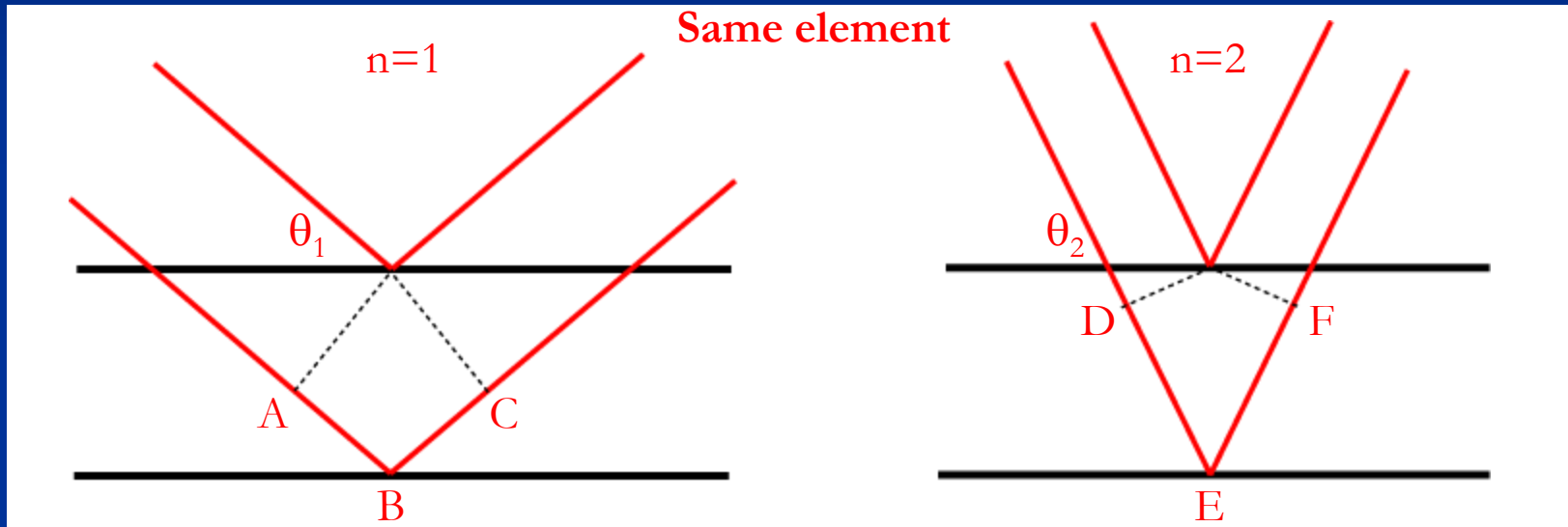


$$n\lambda = 2d \sin \theta$$

$=$ path length ABC

$n =$ order of reflection
(any integer)

First and second order reflections

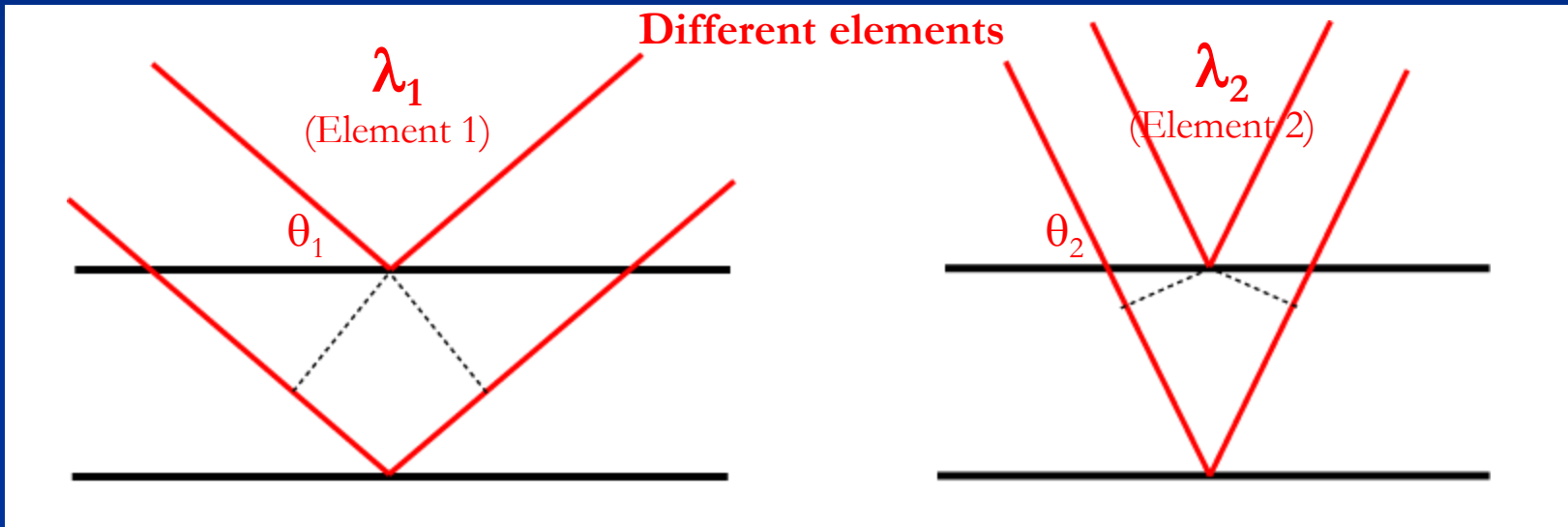


$$1\lambda = 2d \sin\theta_1 \\ = \text{ABC}$$

$$2\lambda = 2d \sin\theta_2 \\ = \text{DEF}$$

$$\text{path DEF} = 2 * \text{path ABC}$$

Diffraction angle



$$n\lambda_1 = 2d \sin\theta_1$$

$$n\lambda_2 = 2d \sin\theta_2$$

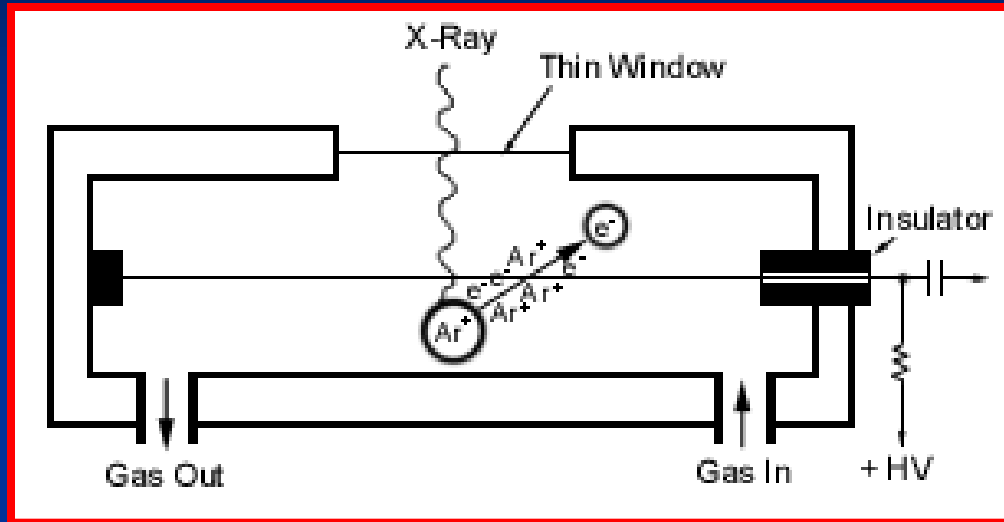
Diffraction angle changes with wavelength being diffracted (for the same order of reflection, n)

WDS Analyzing crystals with different “d” spacings

<u>Name</u>	<u>2d (Å)</u>	<u>Type</u>	<u>Elements usually analyzed</u>
LDEC	98	Ni/C Multi-layer	B-O ($K\alpha$), optimized for C analysis
STE	100.4	Pb stearate	B-O ($K\alpha$), optimized for C analysis
LDE1	59.8	W/Si Multi-layer	C-F ($K\alpha$), optimized for O analysis
TAP	25.8	Thallium acid phthalate	Na-P ($K\alpha$); Cu-Zr ($L\alpha$); Sm-Au ($M\alpha$)
PET	8.742	Pentaerythritol	S-Mn ($K\alpha$); Nb-Pm ($L\alpha$); Hg-U ($M\alpha$)
LIF	4.028	Lithium fluoride	Ti-Rb ($K\alpha$); Ba-U ($L\alpha$)

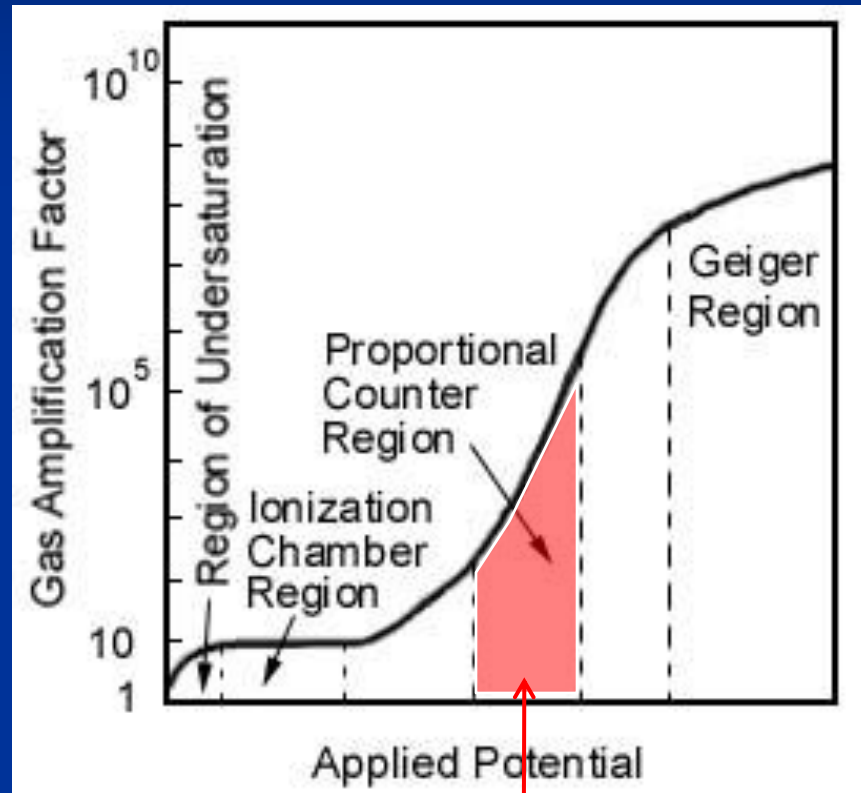
WDS detector: Proportional counter

Count rate depends on bias and gas used



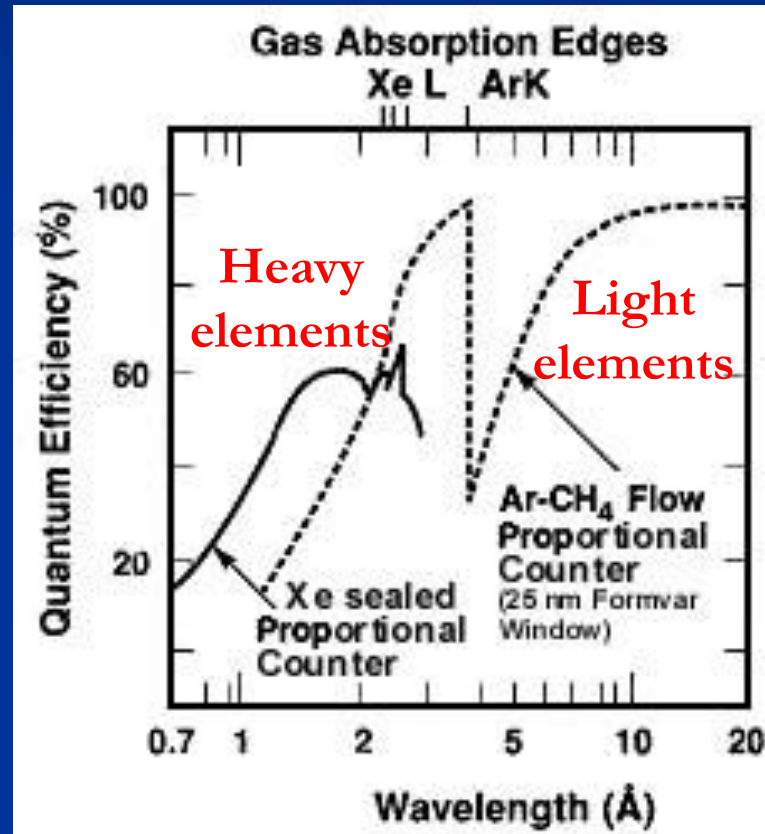
- *Tungsten collection wire set at 1-3 kV bias*
- *Flow counter: 90% Ar + 10% CH₄ (P-10); poly-propylene window*
- *Sealed counter: Xe or Kr; Be window*

Bias in proportional counter



best count rate

Counting efficiency of gas

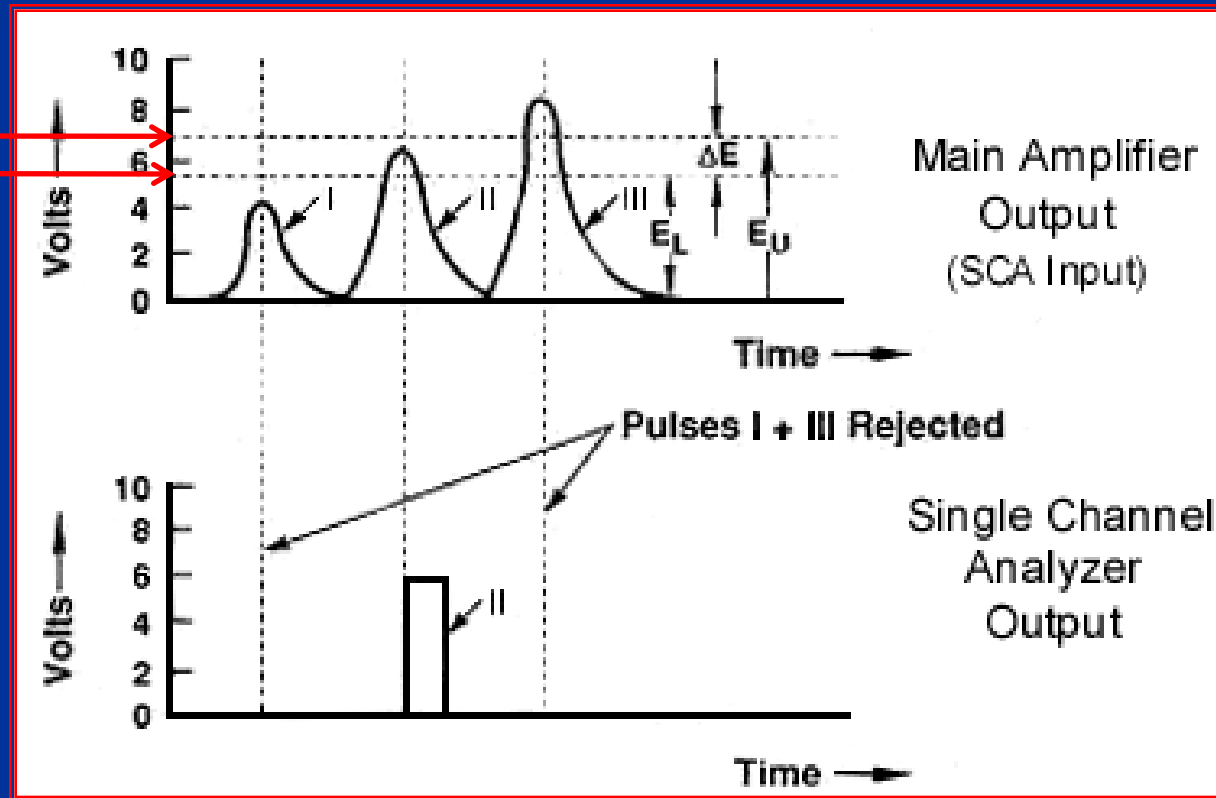


WDS signal processing

Single channel analyzer (SCA)

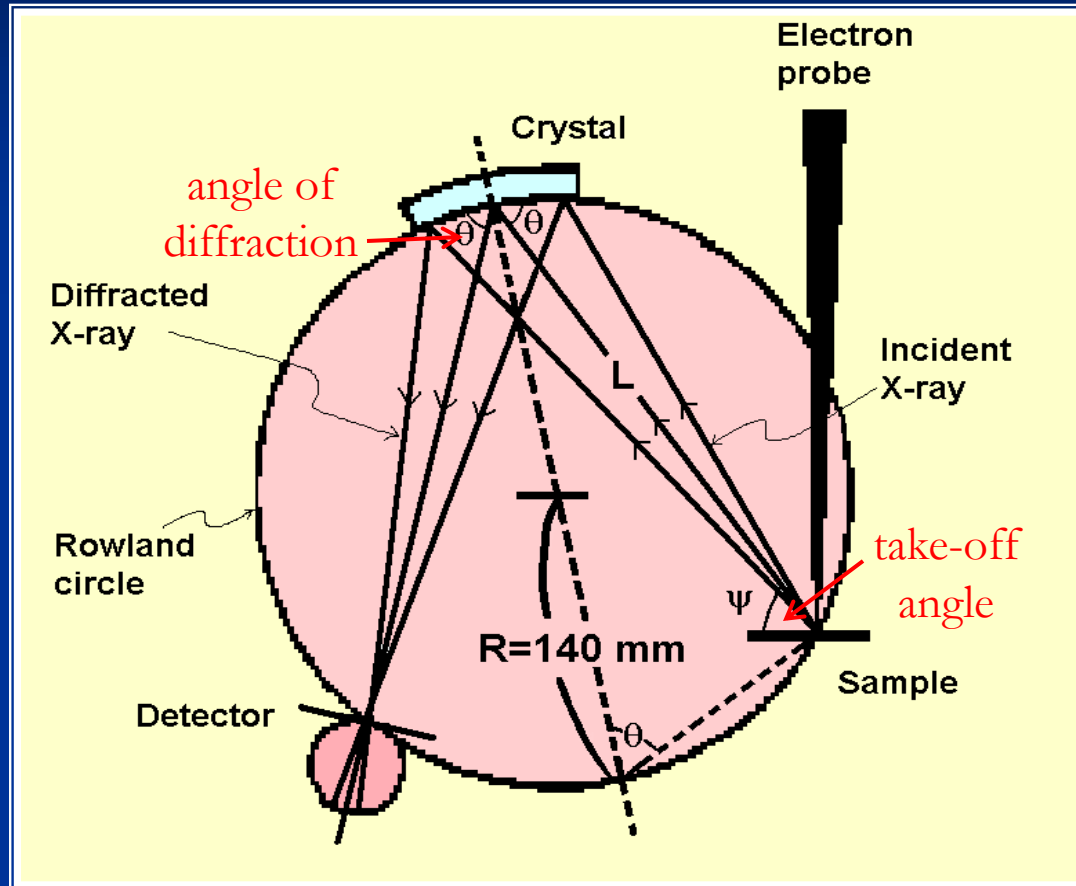
and

pulse height analysis (PHA)



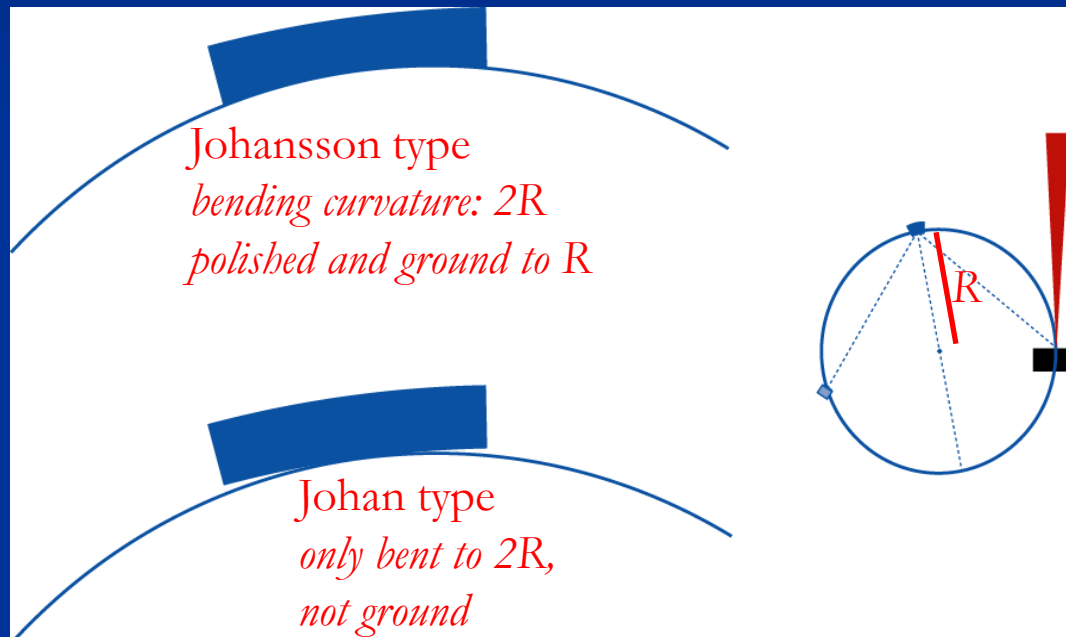
Only pulses in this voltage interval are counted

WDS Focusing geometry



$$L = n\lambda .R/d$$

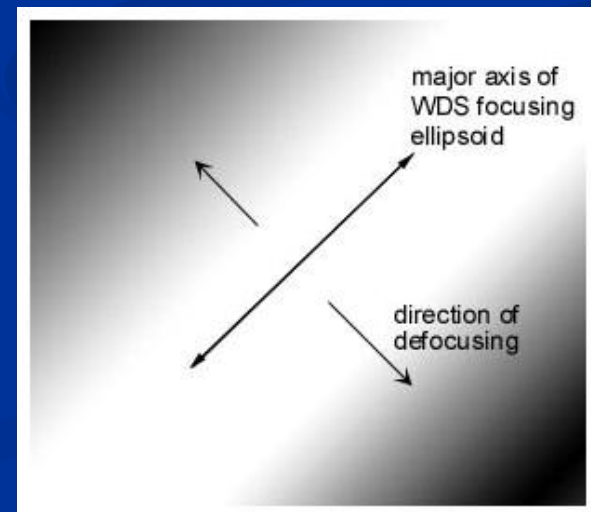
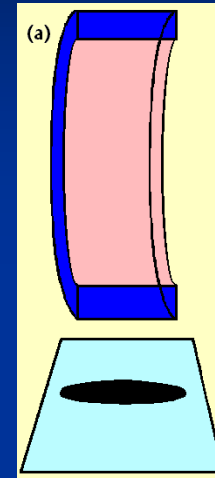
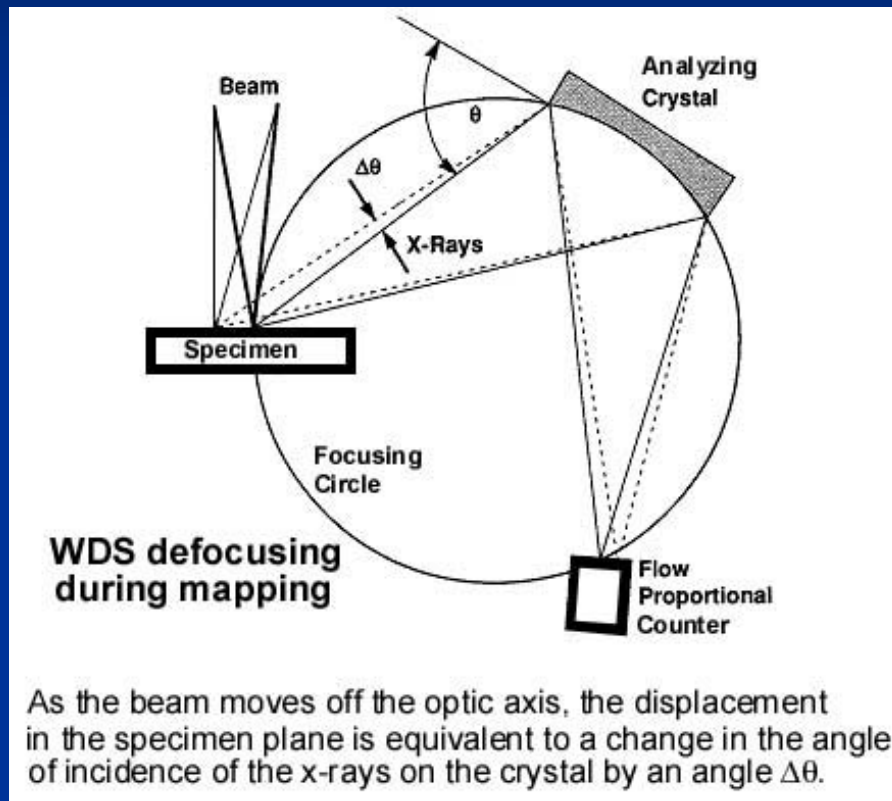
Curved diffracting crystals



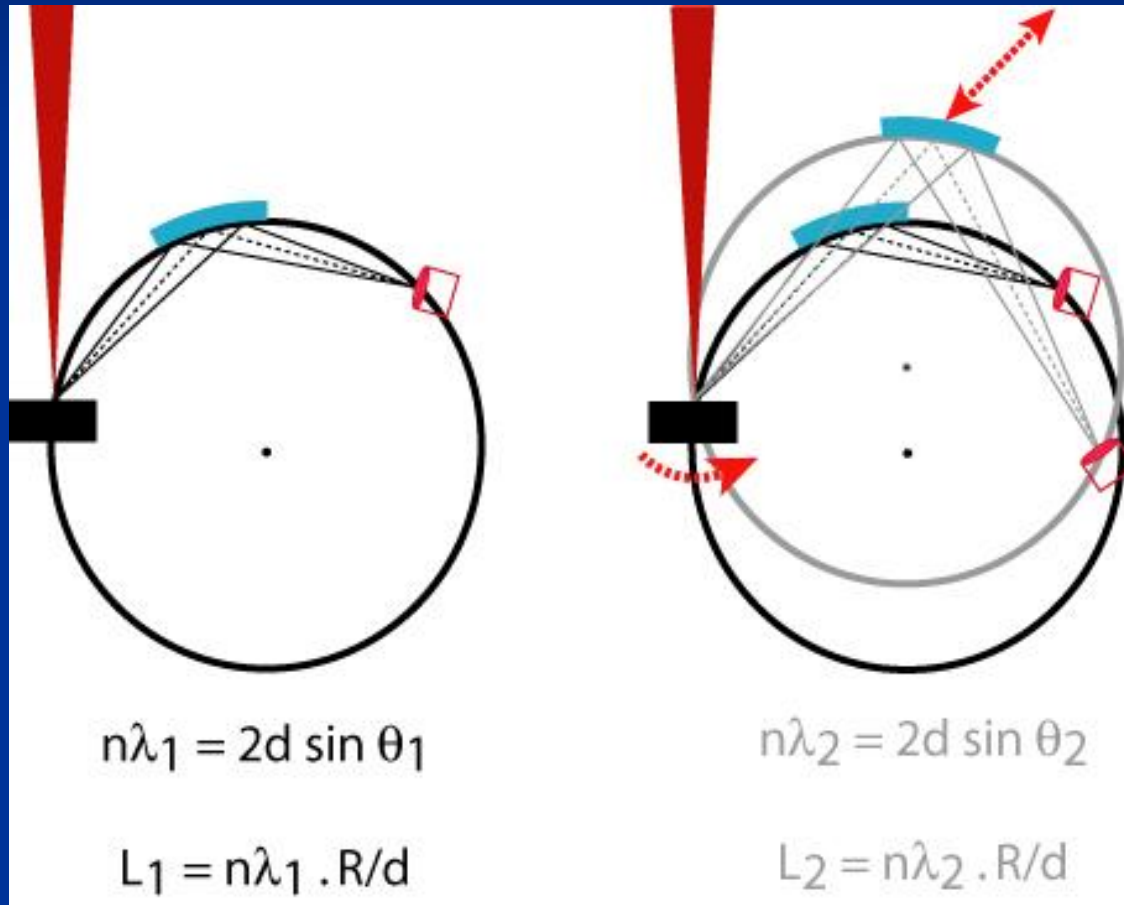
FWHM of fully focusing Johansson-type crystal ~ 10 eV

Some defocusing in Johan-type, but resolution is not compromised

Defocusing in beam-rastered WDS X-ray maps

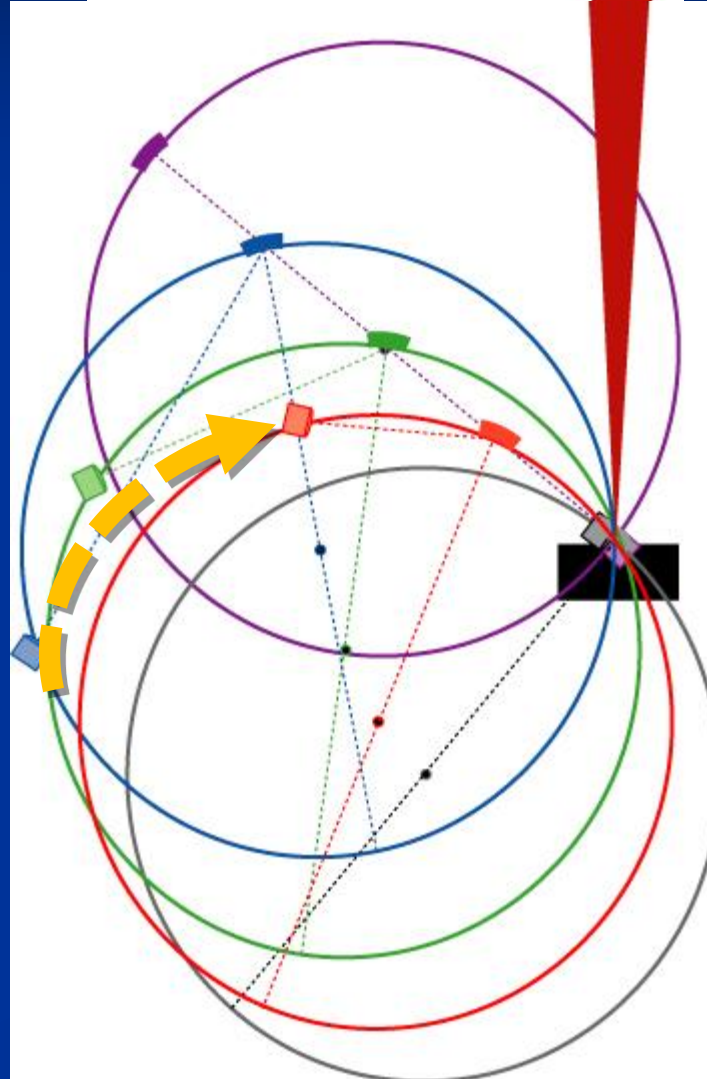
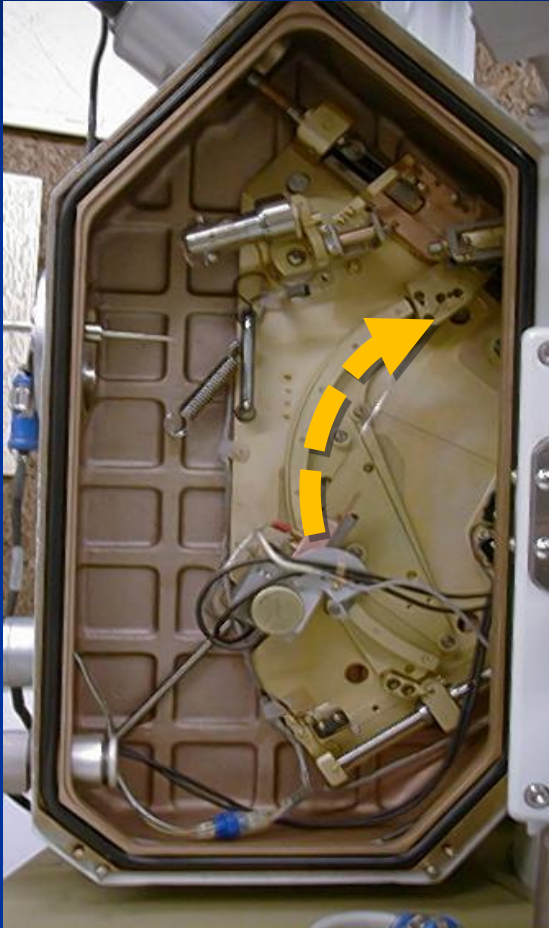


WDS: changing the angle of diffraction



or, $n_2\lambda_1 = 2d \sin \theta_2$
 $L_2 = n_2\lambda_1 \cdot R/d$

Theoretical and actual limits of spectrometer movement



$$2R \leq L \leq 0$$

EPMA: Quantitative analysis procedure

- Sample preparation
- Qualitative analysis with EDS
- Standard intensity measurement (calibration)
- Measurement of X-ray intensities in the specimen
- Data reduction through matrix corrections

Sample preparation

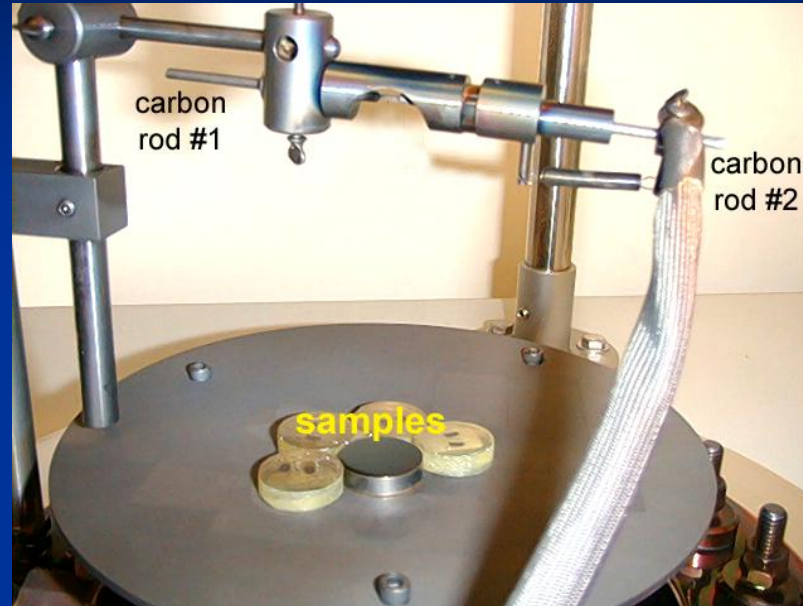
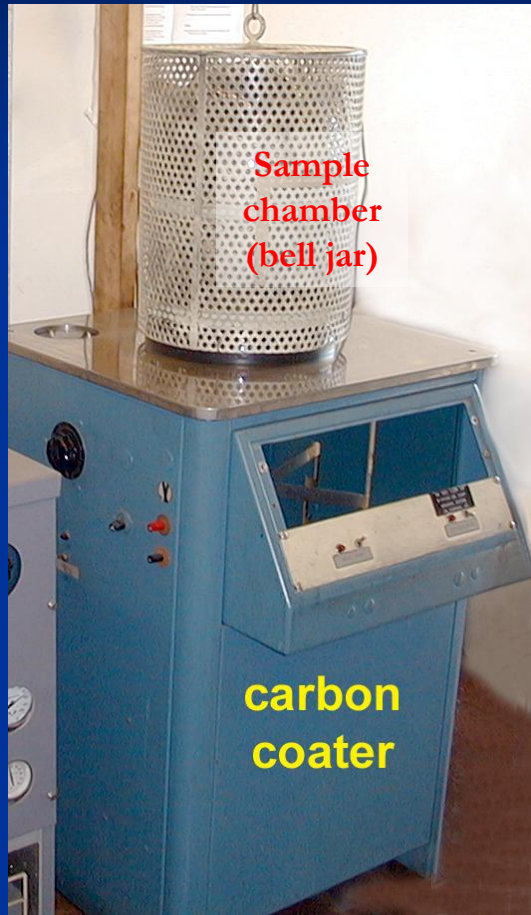
- Sample cut and mounted in epoxy
- Polished first with coarse SiC paper, then with alumina grit slurry (final size: $\leq 0.25 \mu\text{m}$) ¹
- Washed with water in ultrasonic cleaner ²
- Dried with blow duster and air
- Carbon coated ³

1: diamond paste or colloidal silica for some samples; dry polishing paper for water-soluble samples

2: ethanol may be used sparingly; cleaned with blow duster and cloth for samples that dissolve in water

3: for insulators; if standards are coated, however, all samples must be coated

Sample prep: carbon coating



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Spring 2011

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